

**AMENDMENTS TO THE SPECIFICATION:**

**Please insert the following paragraph at page 1, line 5 immediately after the title:**

The instant application claims priority under 35 U.S.C. § 119 to Japanese application No. 2001-66356, filed March 9, 2001.

**Please amend the paragraph at page 2, lines 8- 13 as follows:**

Also, Japanese Patent Laid-Open Publications No. 09-237714 and No. 11-214219 disclose a multi-layer rare earth thin film magnet of ~~0.01 to 300~~ 5 to 500  $\mu\text{m}$  thick, in that a soft magnetic layer and a hard magnetic layer are formed adjacent to each other in a in-plane direction of a film, and formed, for example, by a sputtering method at substrate temperature of 300 to 800  $^{\circ}\text{C}$  and are strictly controlled in thickness at nm level.

**Please amend the paragraph at page 5, lines 27-31 as follows:**

By using a ~~laser-ablation~~ pulsed laser deposition method for the physical deposition, a film-formation speed can be increased as high as about 50  $\mu\text{m/hr}$  that is more than 10 times the speed in a sputtering method. As an element of R in a target alloy composition for ~~laser-ablation~~ pulsed laser deposition, it is desirable to include at least one of Nd and Pr in particular, and Nd or Pr may be partly substituted with Dy.

**Please amend the paragraph at page 6, lines 13-18 as follows:**

As an example of film formation conditions of the ~~laser-ablation~~ pulsed laser deposition, R-B-TM based alloy is formed under conditions such as forming speed of more than 50  $\mu\text{m/hr}$  and degree of vacuum of below  $10^{-6}$  Torr. After the film formation, the film is heat-treated at 650 - 750  $^{\circ}\text{C}$  of maximum temperature to be a 50  $\mu\text{m}$  thick magnetic film having a coercivity of at least 6 kOe which can suppressing the irreversible demagnetizing rate of the magnet.

**Please amend the paragraph at page 7, lines 25-30 as follows:**

Fig. 3 shows hysteresis characteristic of a  $\text{Nd}_{2.6}\text{Fe}_{14}\text{B}$  alloy thick film after an one-hour film-formation on a Ta substrate by a ~~laser-ablation~~ pulsed laser deposition and that of after a heat-treatment of the thick film at 550  $^{\circ}\text{C}$ . In Fig. 3, reference numeral 31 shows in-plane hysteresis characteristic after the film-formation; 32 vertical hysteresis characteristic after the film-formation; and 33 hysteresis characteristic after the heat treatment.